

WHAT IS CLAIMED:

1. An imprint lithography template, said template comprising:  
template alignment marks that are substantially transparent to a first flux of light and that produce an analyzable mark in response to a second flux of light with said first flux of light differing from said second flux of light.
2. The template as recited in claim 1, wherein said first flux of light includes ultraviolet light.
3. The template as recited in claim 1, wherein said second flux of light includes visible light.
4. The template as recited in claim 1, wherein said template alignment marks comprise  $\text{SiO}_x$  with  $x$  less than 2.
5. The template as recited in claim 1, wherein said template alignment marks comprise  $\text{SiO}_x$  with  $x$  approximately 1.5.
6. The template as recited in claim 1, wherein said template is substantially transparent to said first flux of light.
7. The template as recited in claim 1, wherein said template is substantially transparent to said second flux of light.



8. An imprint lithography template, said template comprising:

template alignment marks, with said template substantially transparent to a first flux of light and said template alignment marks producing an analyzable mark in response to a second flux of light with said first flux of light differing from said second flux of light.

9. The template as recited in claim 8, wherein said first flux of light includes ultraviolet light.

10. The template as recited in claim 8, wherein said second flux of light includes visible light.

11. The template as recited in claim 8, wherein said template alignment marks comprise  $\text{SiO}_x$  with  $x$  less than 2.

12. The template as recited in claim 8, wherein said template alignment marks comprise  $\text{SiO}_x$  with  $x$  approximately 1.5.

13. The template as recited in claim 8, wherein said template is substantially transparent to said second flux of light.

14. The template as recited in claim 8, wherein said template alignment marks are substantially transparent to said first flux of light.



15. An imprint lithography template, said template comprising:

template alignment marks that are substantially transparent to ultraviolet light and that produce an analyzable mark in response to visible light.

16. The template as recited in claim 15, wherein said template alignment marks comprise  $\text{SiO}_x$  with  $x$  less than 2.

17. The template as recited in claim 15, wherein said template alignment marks comprise  $\text{SiO}_x$  with  $x$  approximately 1.5.

18. The template as recited in claim 15, wherein said template is substantially transparent to said first flux of light.

19. The template as recited in claim 15, wherein said template is substantially transparent to said second flux of light.